## Amendments to the Specification:

Please replace the paragraph beginning on page 7, line 13 with the following amended paragraph:

An array of parallel and elongated dielectric layer 220 overlies the transparent substrate 210, wherein the dielectric layer 210 220 have a period (p) and a trench 230 is located between adjacent dielectric layers 220. In the first embodiment, the transparent substrate 210 is exposed in the trench 230. The material of the dielectric layers 220 can be polymer, such as PMMA serving as photoresist. Other suitable material such as UV-curable polymers and sol-gel materials can also be used.